



## United States Patent [19]

[54] METHOD FOR MAKING A WAFER-PAIR

Wood et al.

[11] Patent Number:

6,036,872

[45] Date of Patent:

Mar. 14, 2000

	HAVING SEALED CHAMBERS	
[75]	Inventors:	R. Andrew Wood, Bloomington; Jeffrey A. Ridley, Burnsville; Robert E. Higashi, Shorewood, all of Minn.
[73]	Assignee:	Honeywell Inc., Minneapolis, Minn.
[21]	Appl. No.:	09/052,645
[22]	Filed:	Mar. 31, 1998
[51]	Int. Cl.7	C23F 1/00
[52]	U.S. Cl	216/2; 216/2; 216/24;

[56]

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Primary Examiner—Nam Nguyen Assistant Examiner—Julian A. Mercado Attorney, Agent, or Firm—John G. Shudy, Jr.

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## **ABSTRACT**

A method for fabricating a wafer-pair having at least one recess in one wafer and the recess formed into a chamber with the attaching of the other wafer which has a port plugged with a deposited layer on its external surface. The deposition of the layer may be performed in a very low pressure environment, thus assuring the same kind of environment in the sealed chamber. The chamber may enclose at least one device such as a thermoelectric sensor, bolometer, emitter or other kind of device. The wafer-pair typically will have numerous chambers, with devices, respectively, and may be divided into a multiplicity of chips.

## 24 Claims, 4 Drawing Sheets

